

### General Description

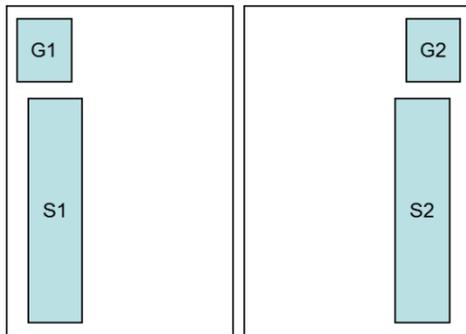
The MDW0416EB uses advanced MagnaChip's MOSFET Technology, which provides high performance in on-state resistance, fast switching performance and excellent quality. Excellent low  $R_{DS(ON)}$ , low gate charge and operation for Battery Application.

### Features

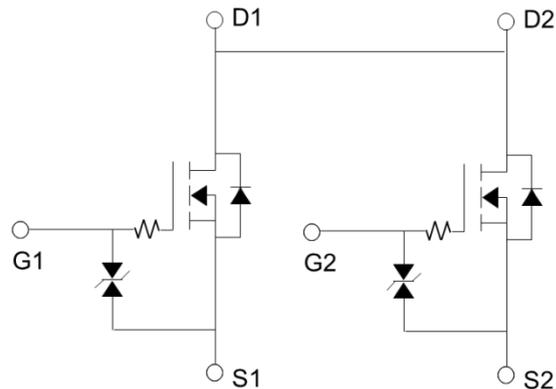
- $V_{DS} = 24V$
- Drain-Source ON Resistance;
  - $R_{DS(ON)} < 7.2m\Omega @ V_{GS} = 3.9V$
  - $R_{DS(ON)} < 10.2m\Omega @ V_{GS} = 3.0V$

### Applications

- Portable Battery Protection Module



**Chip Layout**  
(Drain is the backside of the wafer (TOP View))



### Absolute Maximum Ratings ( $T_a = 25^\circ C$ )

Characteristics	Symbol	Rating	Units
Drain-Source Voltage	$V_{DSS}$	24	V
Gate-Source Voltage	$V_{GSS}$	$\pm 12$	V
Junction and Storage Temperature Range	$T_J, T_{stg}$	-55~150	$^\circ C$

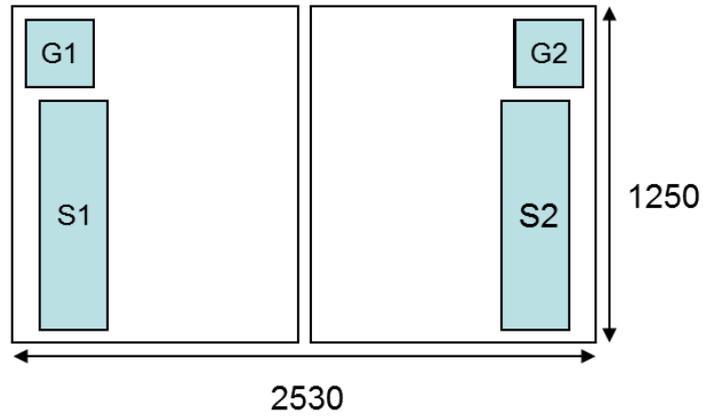
**Electrical Characteristics (Ta =25°C)**

Characteristics	Symbol	Test Condition	Min	Typ	Max	Units
<b>Static Characteristics</b>						
Drain-Source Breakdown Voltage	$BV_{DSS}$	$I_D = 250\mu A, V_{GS} = 0V$	24		-	V
Gate Threshold Voltage	$V_{GS(th)}$	$V_{DS} = V_{GS}, I_D = 250\mu A$	0.5	1.0	1.5	
Drain Cut-Off Current	$I_{DSS}$	$V_{DS} = 20V, V_{GS} = 0V$	-	-	1	$\mu A$
Gate Leakage Current	$I_{GSS}$	$V_{GS} = \pm 10V, V_{DS} = 0V$	-	-	10	
Drain-Source ON Resistance	$R_{DS(ON)}$	$V_{GS} = 3.9V, I_D = 3.0A$		6.4	7.2	$m\Omega$
		$V_{GS} = 3.0V, I_D = 3.0A$		8.0	10.2	
<b>Drain-Source Body Diode Characteristics</b>						
Source-Drain Diode Forward Voltage	$V_{SD}$	$I_S = 1.0A, V_{GS} = 0V$	-	0.7	1.0	V

## Notes :

- The device current rating is derived from its thermal resistance and from the number and diameter of bonding wires. The testing current at wafer level is set only for ease of testing. Actual package current ratings can be much higher.
- No SOA curves are provided because they are dependent on package thermal resistance.

## Die Layout and Construction



Contents	Value
Wafer Substrate	N-type
Wafer Thickness	145±10 $\mu\text{m}$
Metal (Top)	Al (4.5±0.3 $\mu\text{m}$ )
Metal (Back)	V/Ni/Ag
Passivation Layer	Yes
Die Size (with Scribe Lane)	2530×1250 $\mu\text{m}^2$
Scribe lane width	60 $\mu\text{m}$
Cell type	Stripe Cell
Gate Pad Size	164 × 152 $\mu\text{m}^2$
Gap between Die	7 $\mu\text{m}$

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